

Abstract

A method of preserving a cosmetic is provided,
5 comprising mixing into the cosmetic a substantially
paraben-free endermic liniment composition comprising
an antiseptic/antifungal agent for inhibition of microbial
growth in cosmetics. The antiseptic/antifungal agent is
comprised of 0.1-3 wt%
10 2-n-butyl-2-ethyl-1,3-propanediol, 2.0-5.0 wt%
1,3-butylene glycol, and water. Alternatively, the
antiseptic/antifungal agent may comprise 0.1-3.0 wt%
2,2-dialkyl-1,3-propanediol and 0.1-15.0 wt% of a diol.
In addition, a substantially paraben-free endermic
15 liniment composition comprising an antiseptic/antifungal
agent for inhibition of microbial growth in cosmetics is
provided, the agent comprising 0.1-3 wt% of
2-n-butyl-2-ethyl-1,3-propanediol, 2.0-5.0 wt%
1,3-butylene glycol, and water.